

Notice of References Cited	Application/Control No. 10/533,655		Applicant(s)/Patent Under Reexamination NARITOMI ET AL.	
	Examiner KEVIN R. KRUER		Art Unit 1787	Page 1 of 1

U.S. PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
*	A	US-4,870,377	09-1989	Brown et al.	333/238
*	B	US-4,547,274	10-1985	Ohashi et al.	430/278.1
*	C	US-4,171,563	10-1979	Withoos, Wilhelmus H. C.	29/600
*	D	US-2005/0215764	09-2005	Tuszynski et al.	530/358
	E	US-			
	F	US-			
	G	US-			
	H	US-			
	I	US-			
	J	US-			
	K	US-			
	L	US-			
	M	US-			

FOREIGN PATENT DOCUMENTS

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N					
	O					
	P					
	Q					
	R					
	S					
	T					

NON-PATENT DOCUMENTS

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
	U	Madden, H.H. and DW Goodman "An AES investigation of aluminum, Al oxide, and Al nitride thin films" Surface Science, vol 150, Issue 1, February 1985 (p39-46)
	V	Gajda, MA and H. Ahmed "Anisotropic etching of silicon in hydrazine" Sensors and Actuators A: Physical, vol 40, Issue 3, March 1994, pages 227-236
	W	Yamasaki, Hiroo Intelligent Sensors (1996) p50 http://books.google.com/books?id=kP2rS0AN7-4C&pg=PA49&dq=intelligent+sensors+hydrazine&hl=en&ei=c-53TcKONdORgQel4uy7BQ&sa=X&oi=book_result&ct=result&resnum=1&ved=0CDQQ6AEwAA#v=onepage&q=hydrazine&f=false
	X	

*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
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